

SHIGA7.004APC

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	: Maruyama et al.
Appl. No.	: 10/522,036
Filed	: January 19, 2005
For	: CHEMICAL AMPLIFICATION TYPE POSITIVE PHOTORESIST COMPOSITION AND RESIST PATTERN FORMING METHOD
Examiner	: Lee, Sin J
Group Art Unit	: 1752

AMENDMENT AND RESPONSE TO ADVISORY ACTION AND FINAL OFFICE ACTION

**Mail Stop AF**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

In response to the Advisory Action mailed **December 26, 2006**, and the Office Action mailed **September 15, 2006**, please consider the following amendments and remarks.

**Amendments to the claims** begin on page 2 of this paper.

**Remarks** begin on page 13 of this paper.

Please  
Enter  
S.J.L.  
1-26-07